

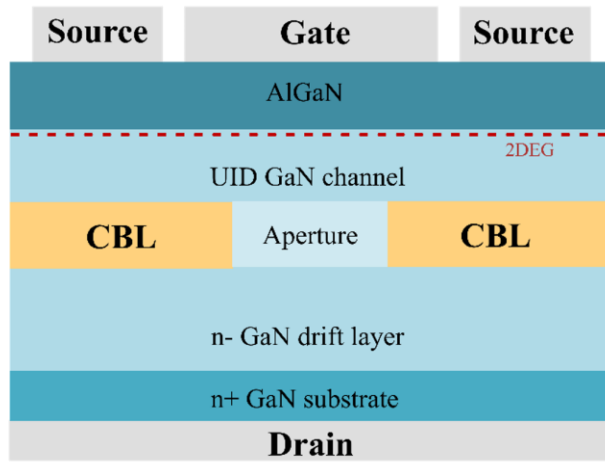
Theoretical Insights and Modeling of Vertical GaN Switches for Industrial Applications

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University of Southern Denmark*

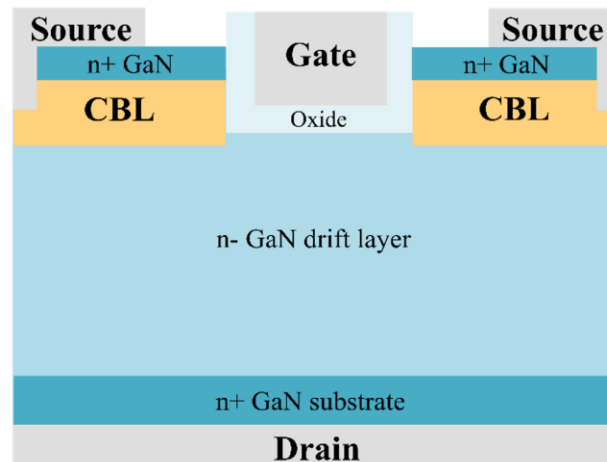
**Bodo's
Wide Bandgap
Event 2024**

Making WBG Designs Happen

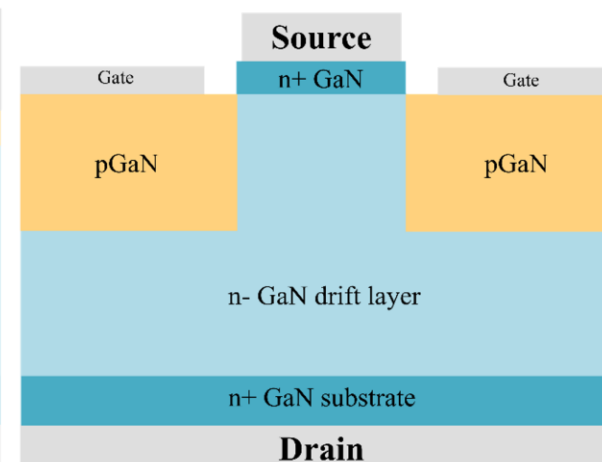
GaN



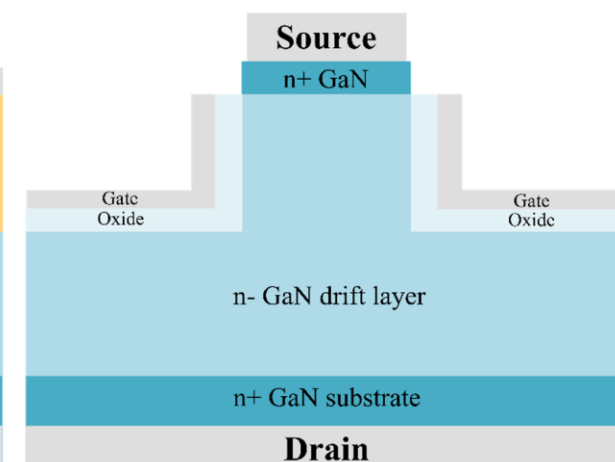
(a) CAVET



(b) Trench MOSFET

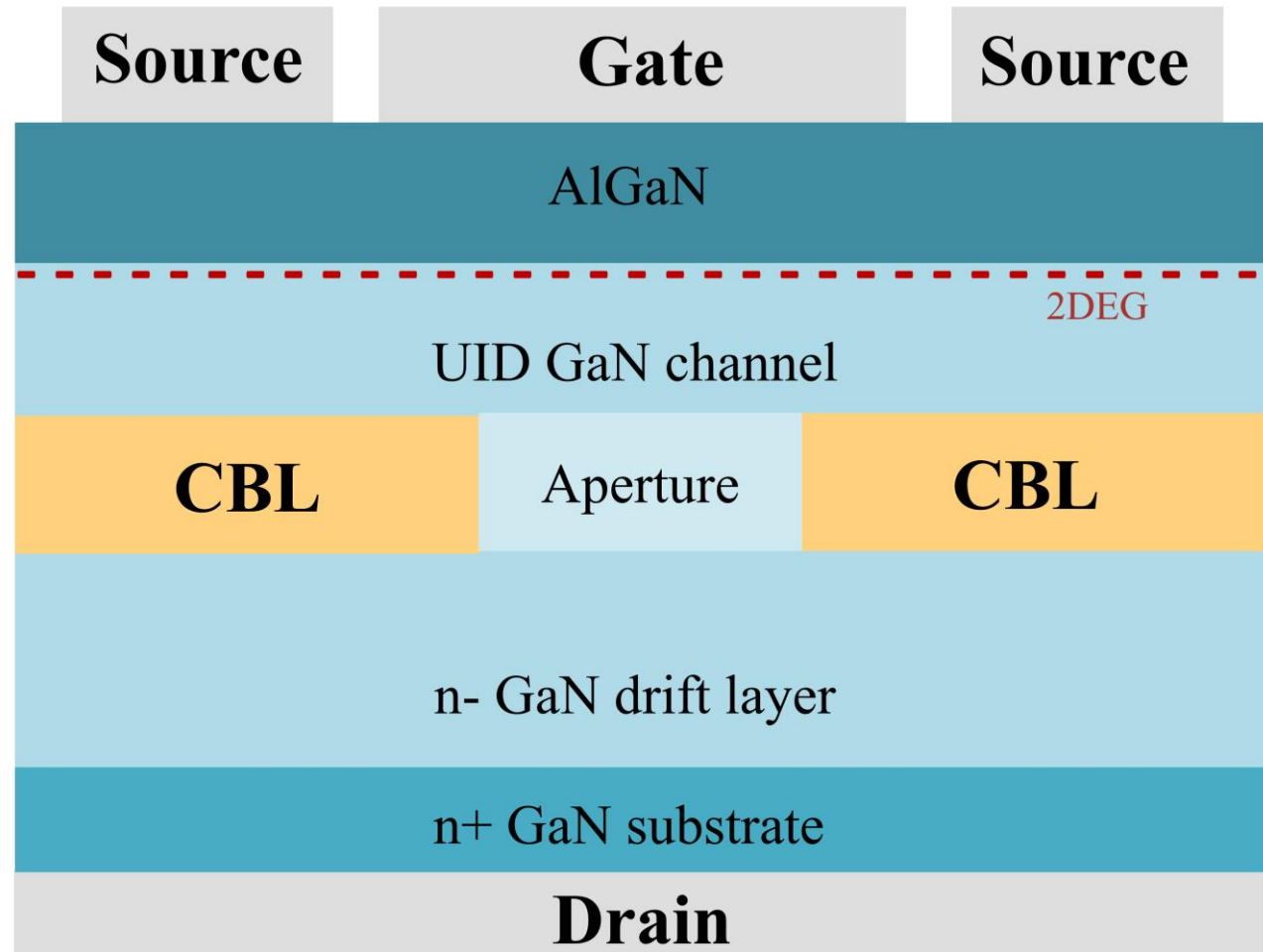


(c) Vertical JFET



(d) Vertical FinFET

GaN-based vertical transistors: (a) CAVET, (b) Trench MOSFET, (c) Fin FET and (d) JFET



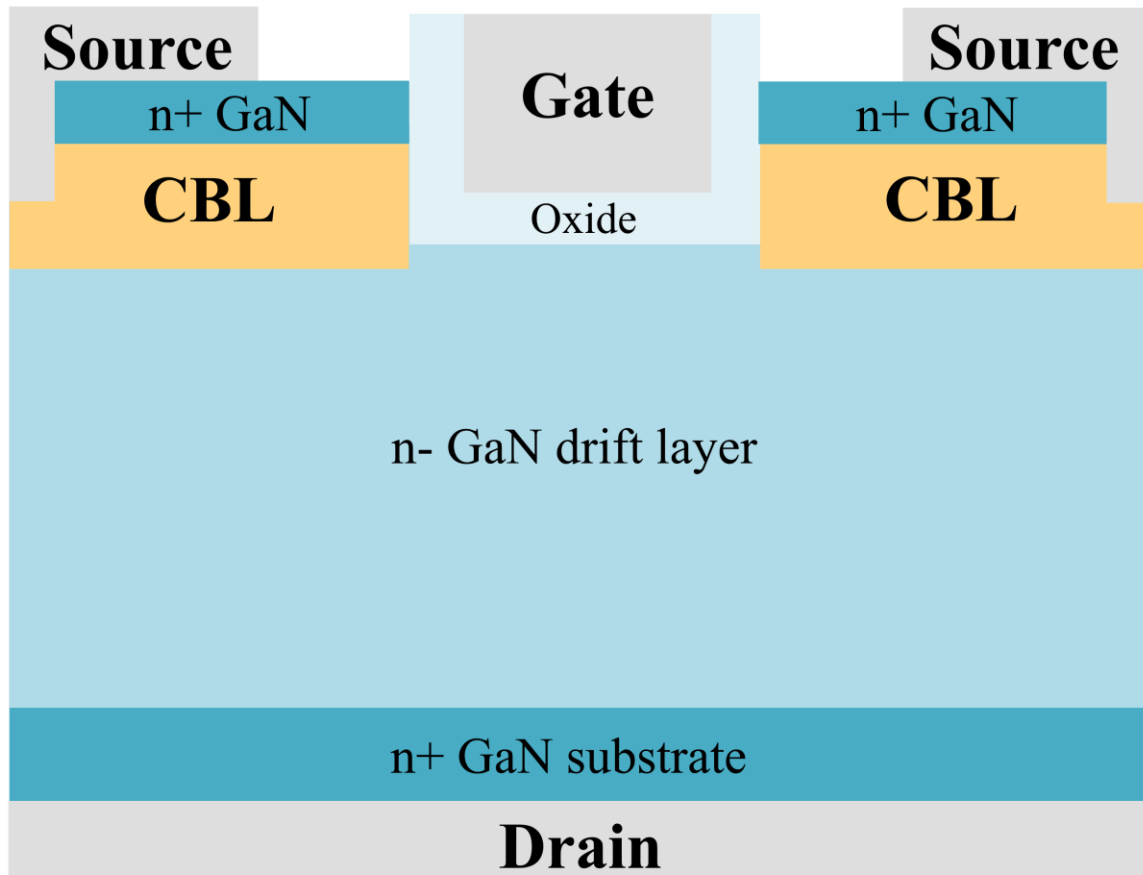
Conventional CAVET Structure

➤ Advantages

- High channel conductivity due to 2DEG
- High Breakdown Voltage
- Reduced DC-RF Dispersion
- Efficient Die Area Utilization

➤ Challenges

- Leakage Paths
- Device Design
- Fabrication Technique
- Achieving Normally-Off Operation



Trench MOSFET cross sectional schematic

➤ Advantages

- Normally off

➤ Challenges

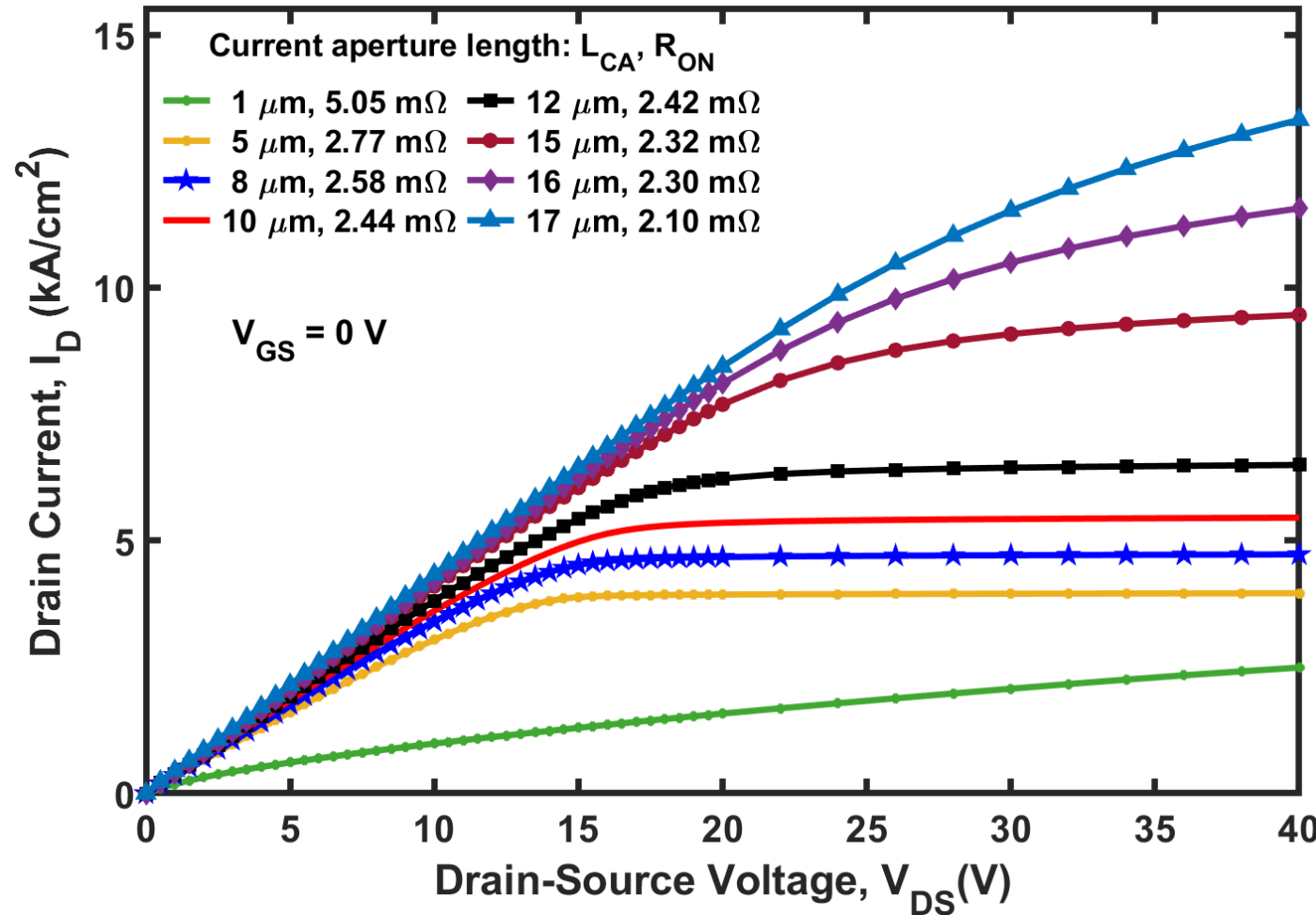
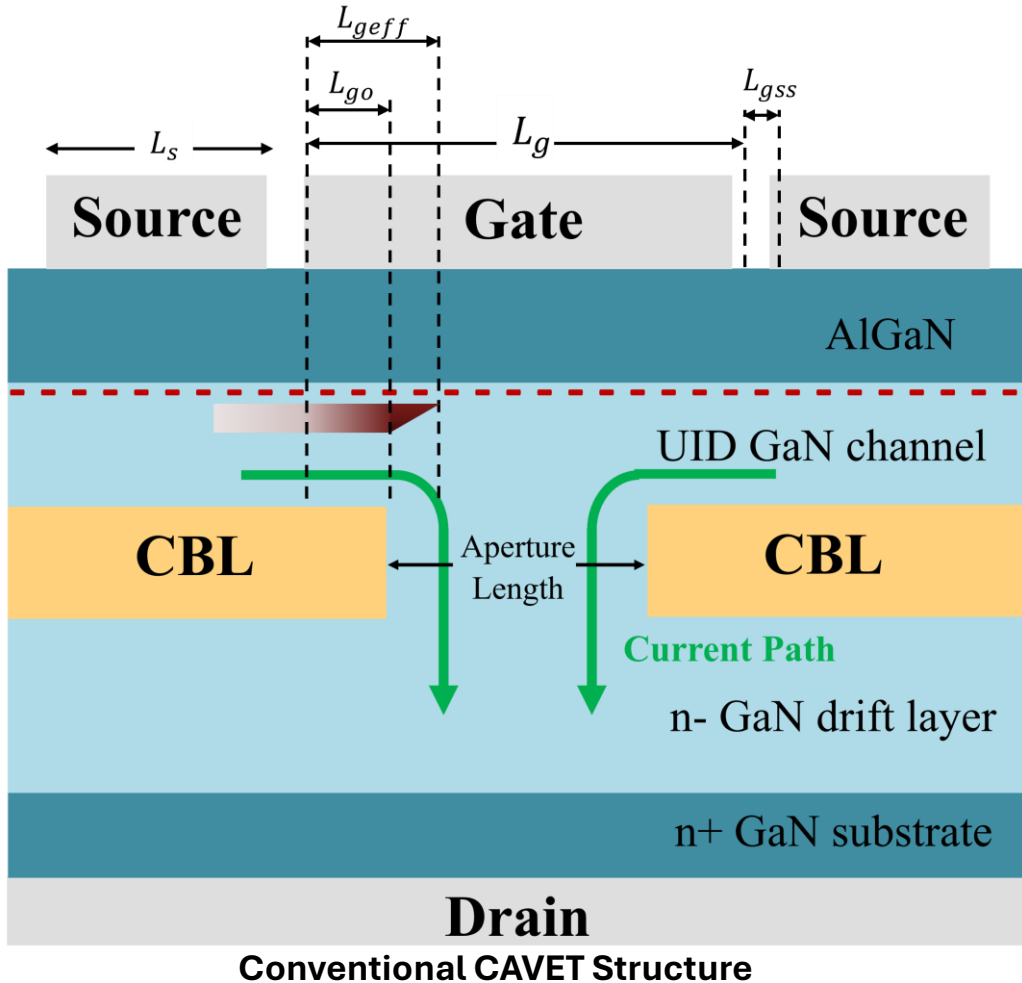
- Doesn't utilize a 2DEG channel
- Low electron mobility
- Potential trapping effects
- Buried p-GaN Layer Activation
- Potential punch-through breakdown issues
- Very high turn on voltage.

➤ Application

- High power applications

Output Characteristics

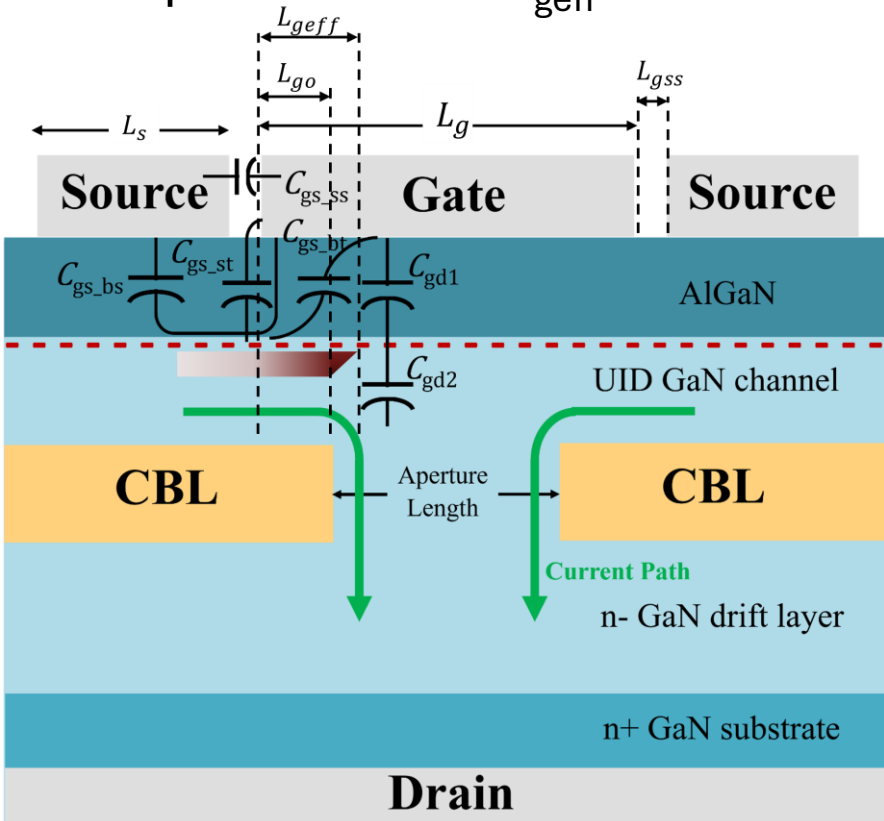
- On-resistance decreases with the increase of the current aperture length.



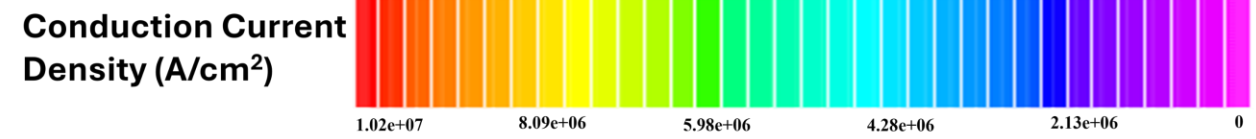
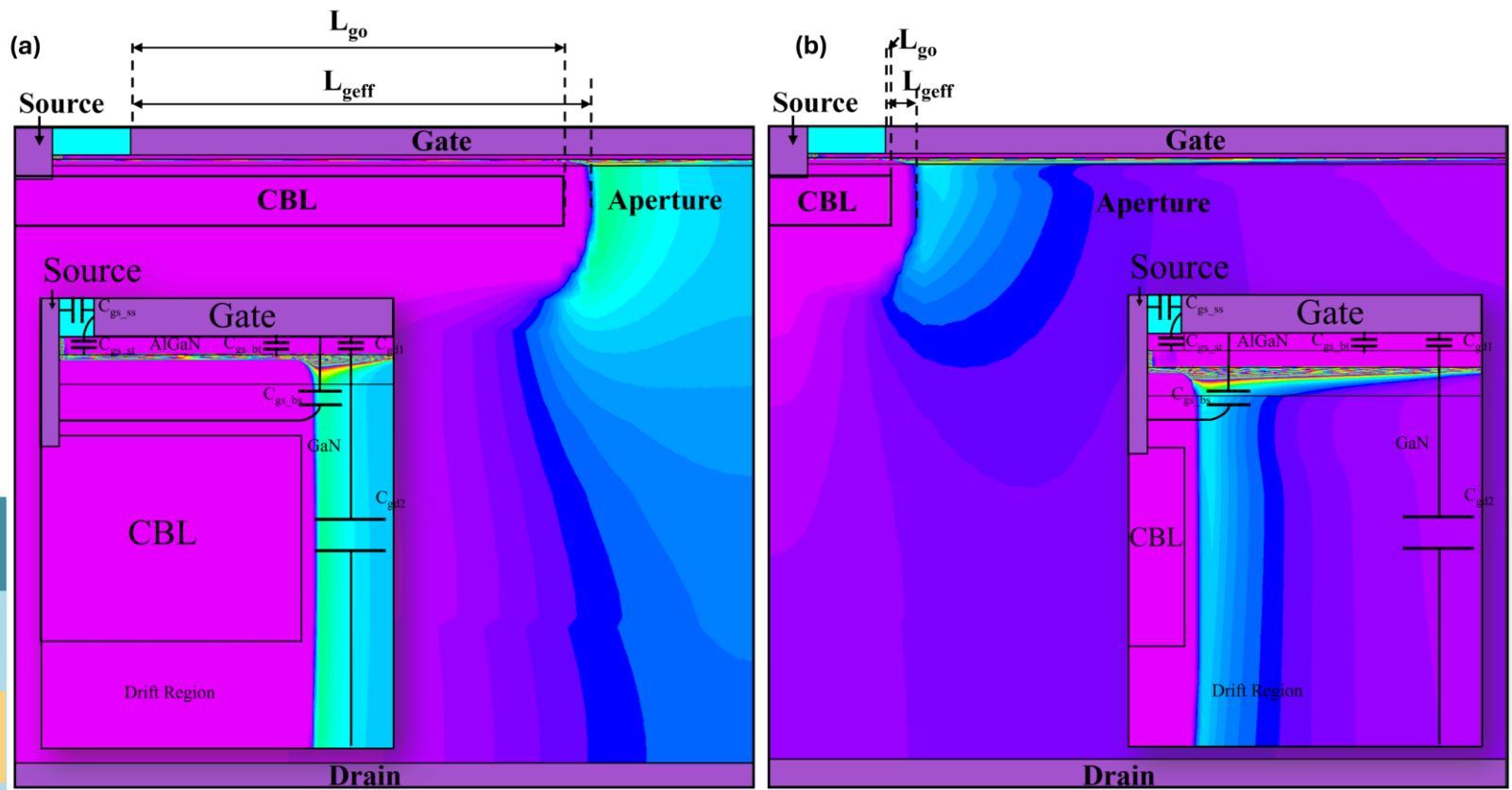
The output characteristics for different aperture lengths at $V_{GS} = 0 \text{ V}$

Intrinsic Gate Capacitance

- The aperture length change the effective gate length (L_{geff})
- Intrinsic gate capacitance depends on the L_{geff}

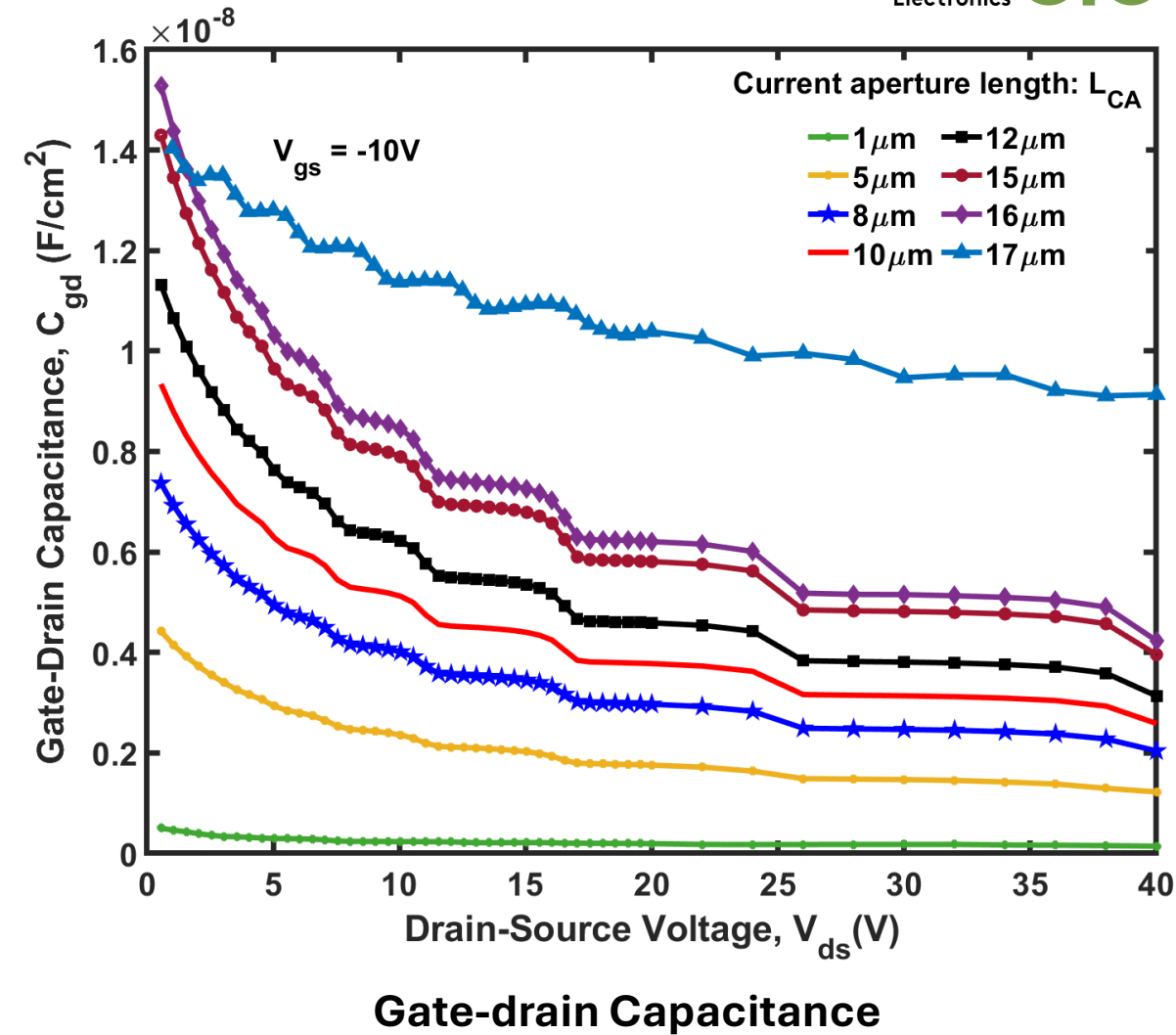
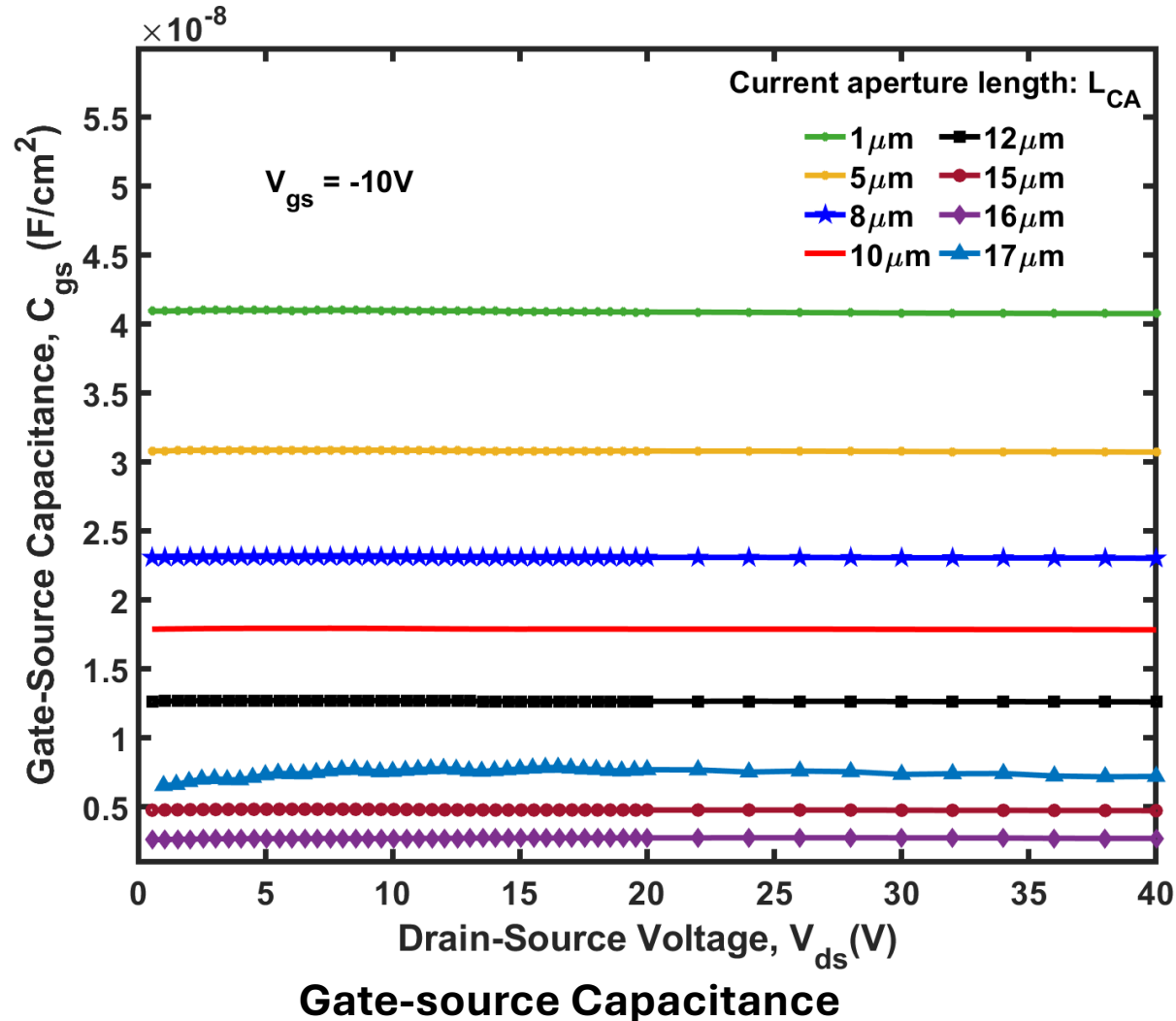


CAVET structure schematic with a simplified model of intrinsic gate capacitances



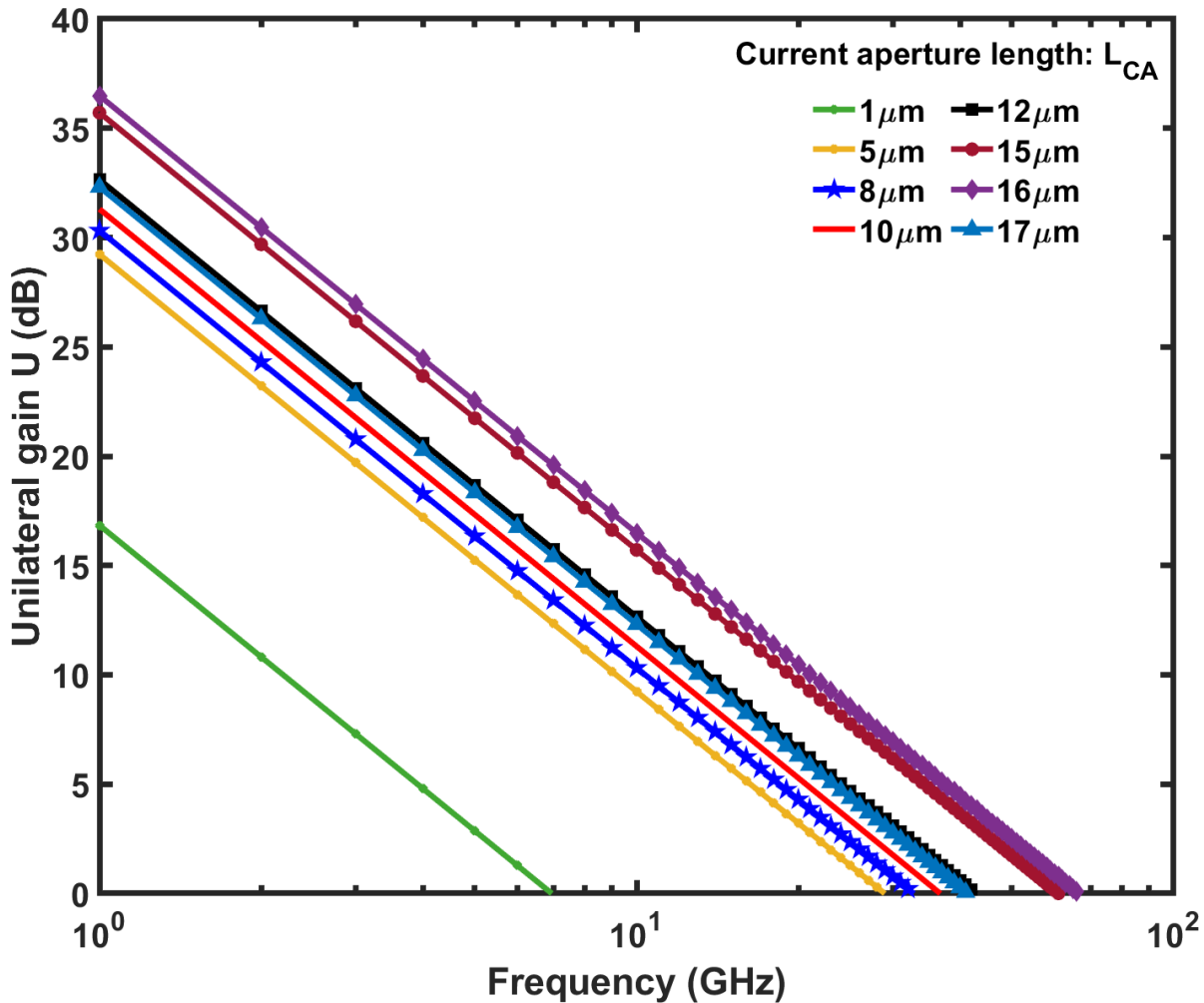
The conduction current density electron concentration of the CAVET structure with aperture lengths of (a) 5 μm , and (b) 16 μm .

- Gate-Source Capacitance decreases with aperture length

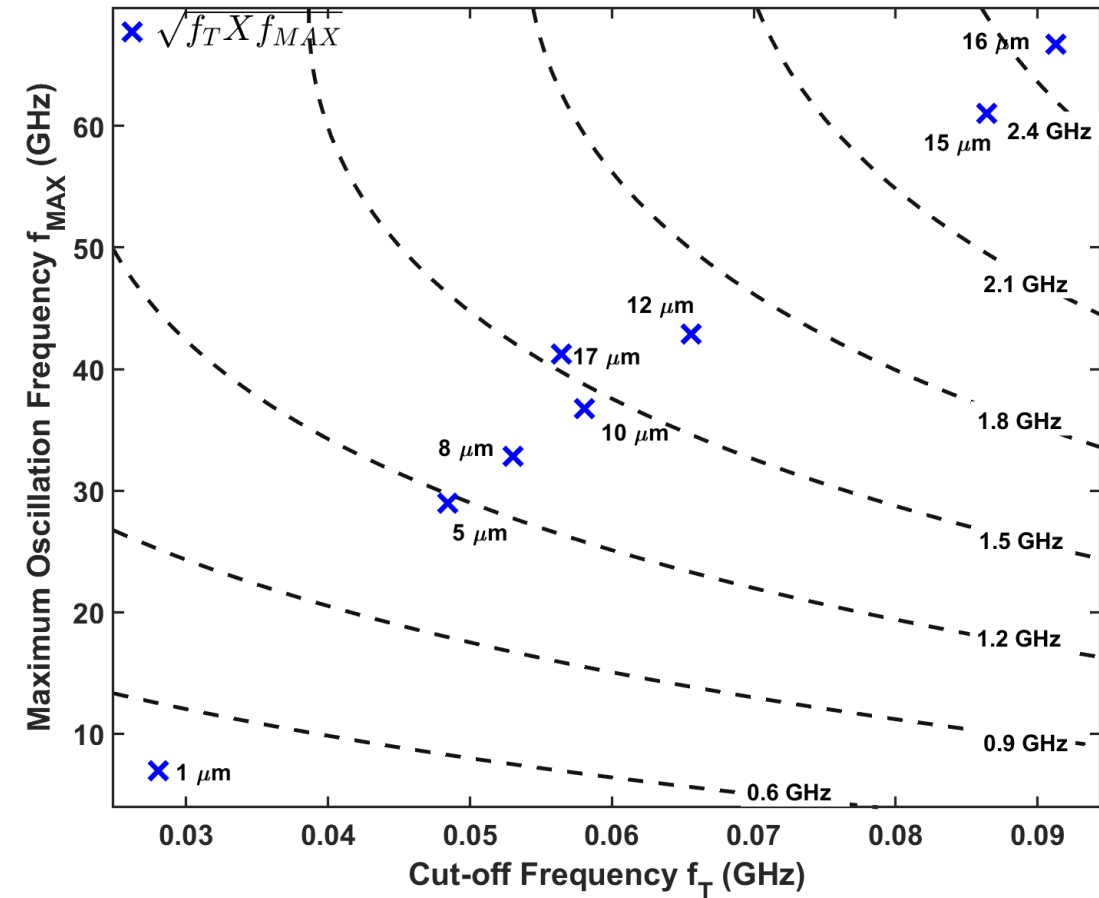


- Gate-drain Capacitance increases with aperture length

- The unilateral power gain increases with the aperture length.

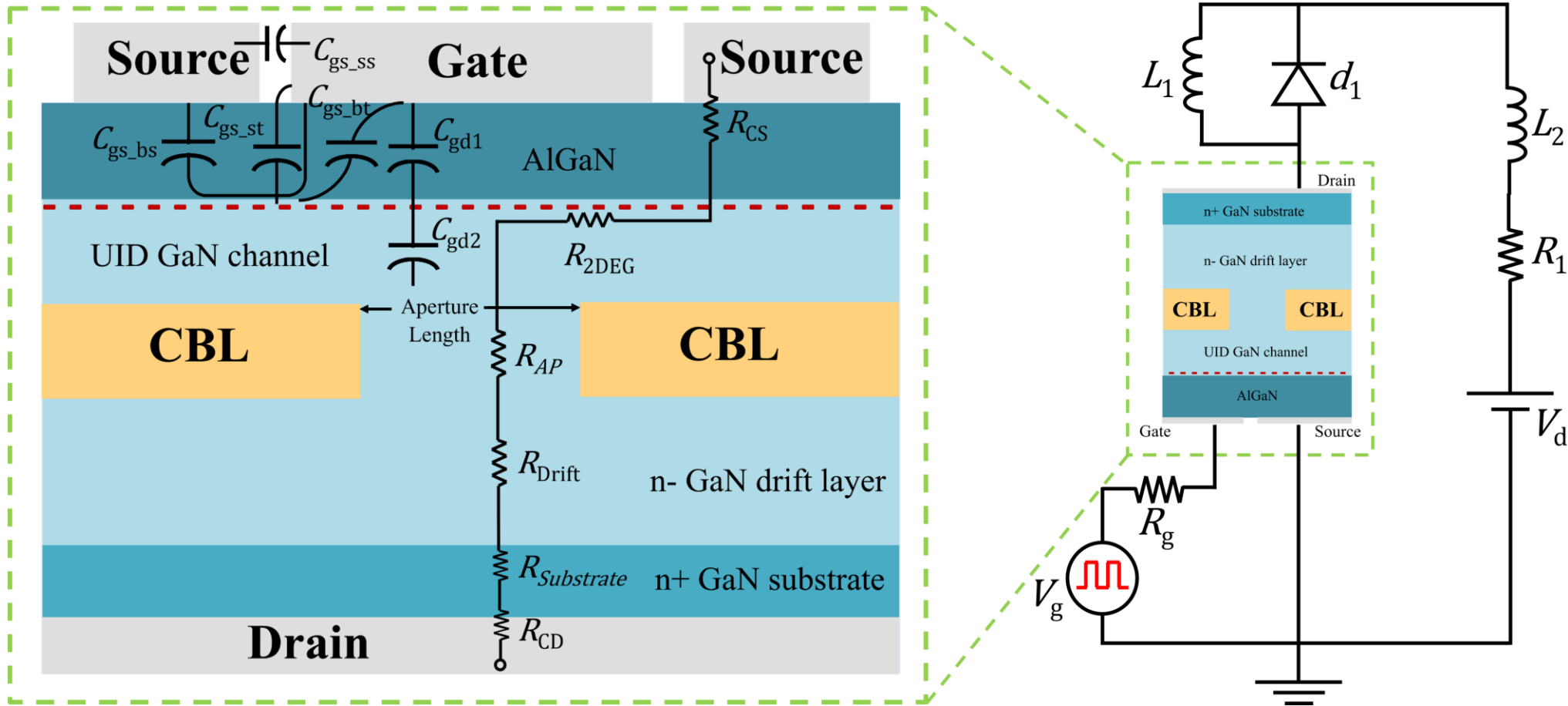


Mason's unilateral power gain (U) versus frequency



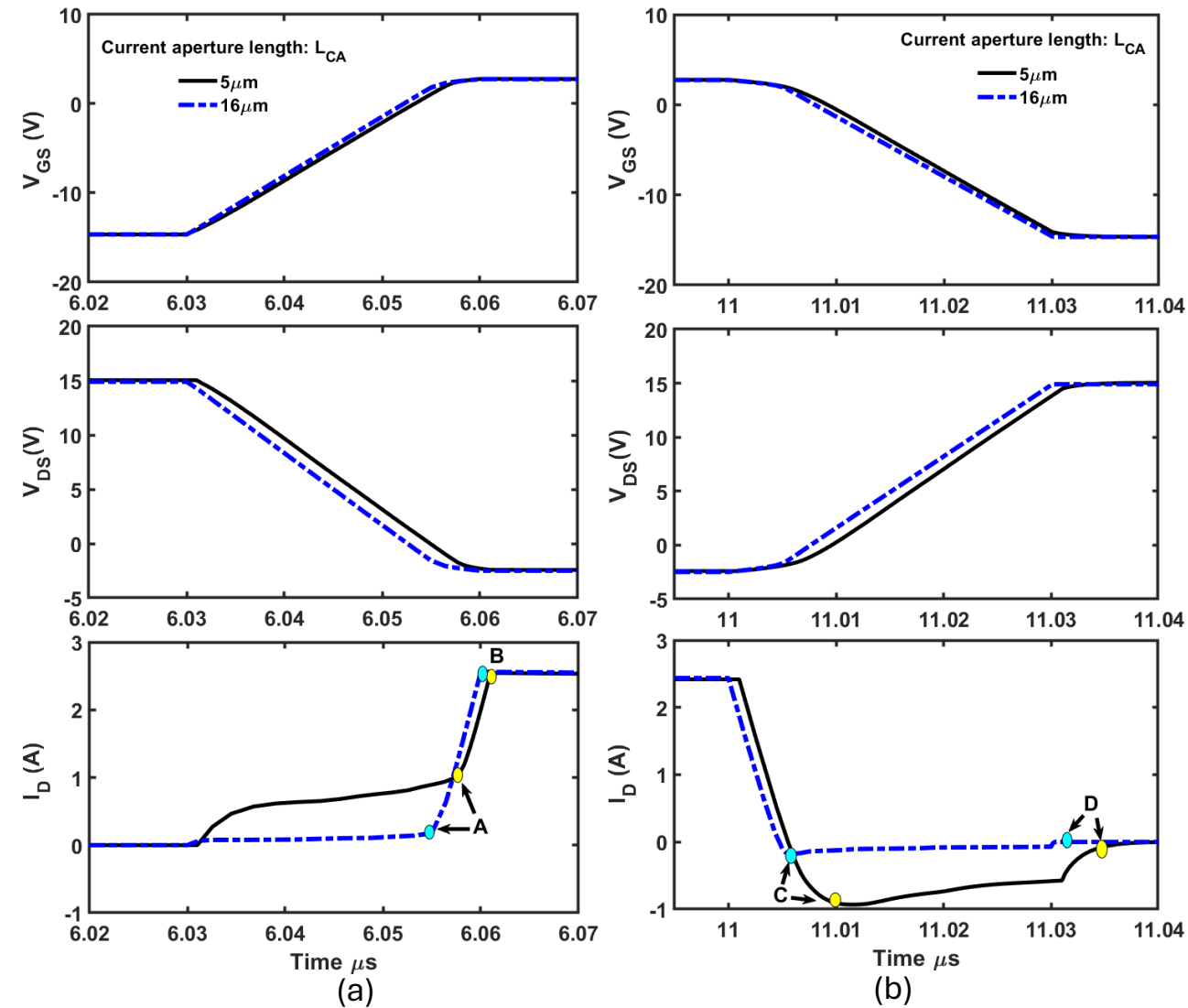
f_{MAX} against f_T for various aperture lengths of the CAVET

- The value of $\sqrt{f_T \times f_{MAX}}$ for large aperture length is higher than 2.4 GHz.
- The peak values of f_T and f_{MAX} are 0.09 GHz and 66.73 GHz, respectively, achieved at $L_{CA} = 16 \mu\text{m}$.



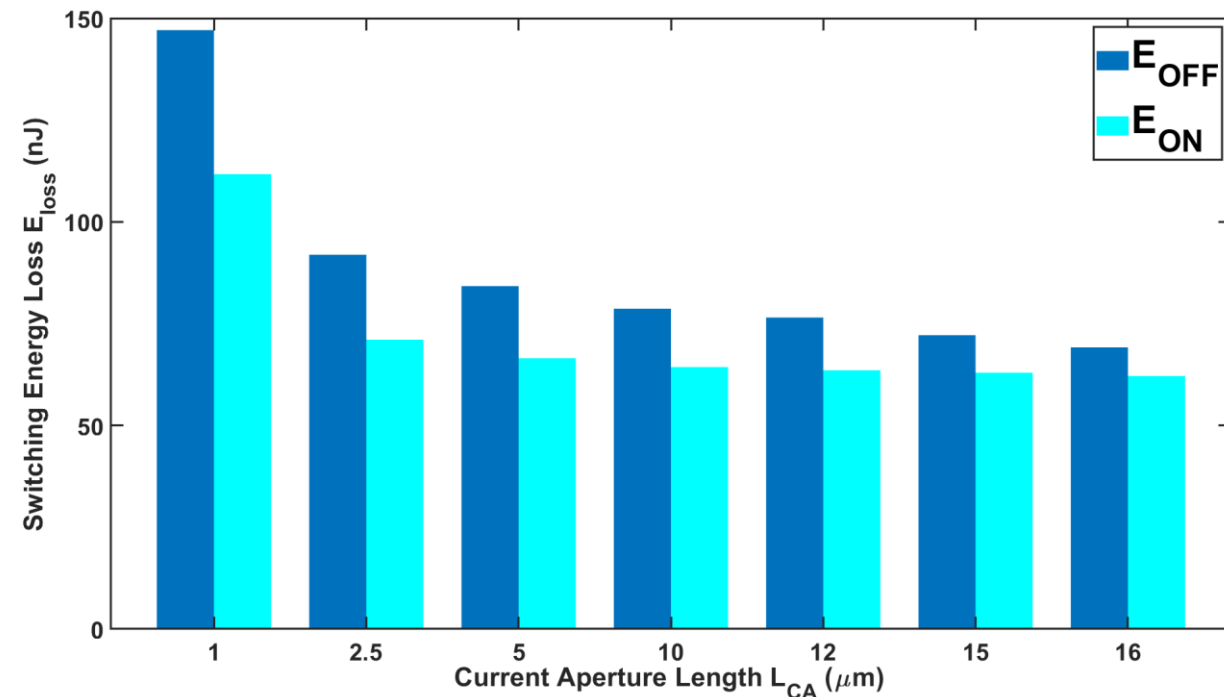
Switching test circuit using CAVET

Switching Waveforms and Energy loss



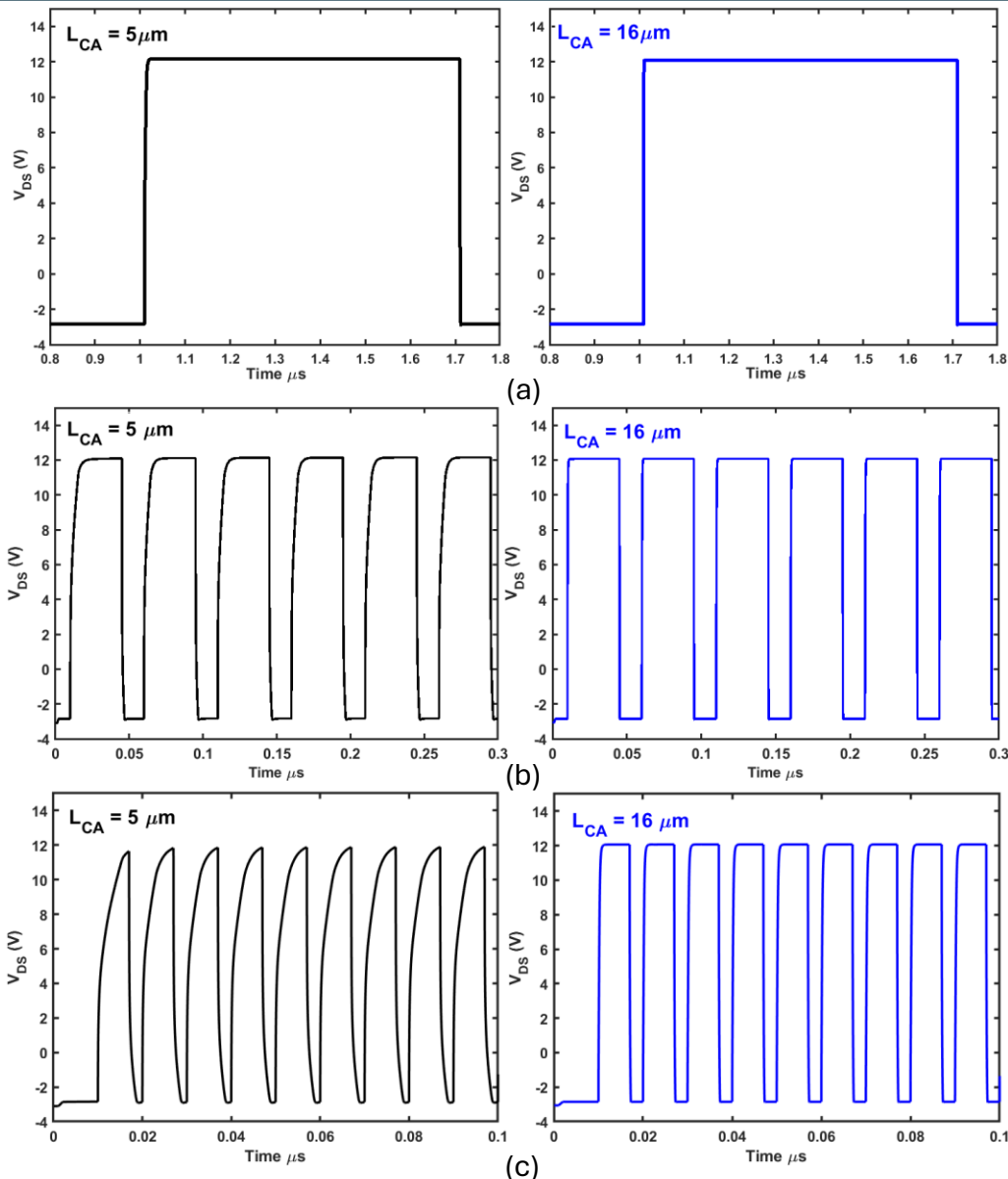
(a) Turn-on and (b) Turn-off voltage/current waveforms for different current aperture lengths of CAVET

- Both turn-on and turn-off time decreases with aperture length.
- Large aperture length has lower switching energy loss.

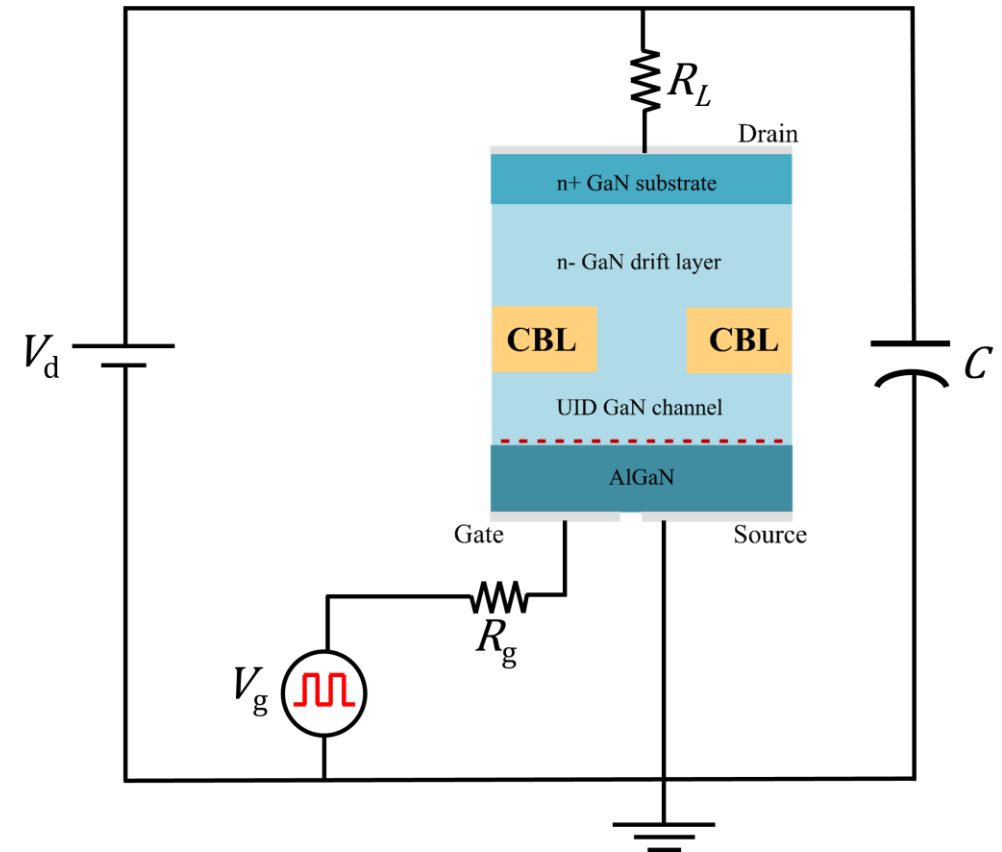


Switching Energy losses of the CAVET with various aperture lengths

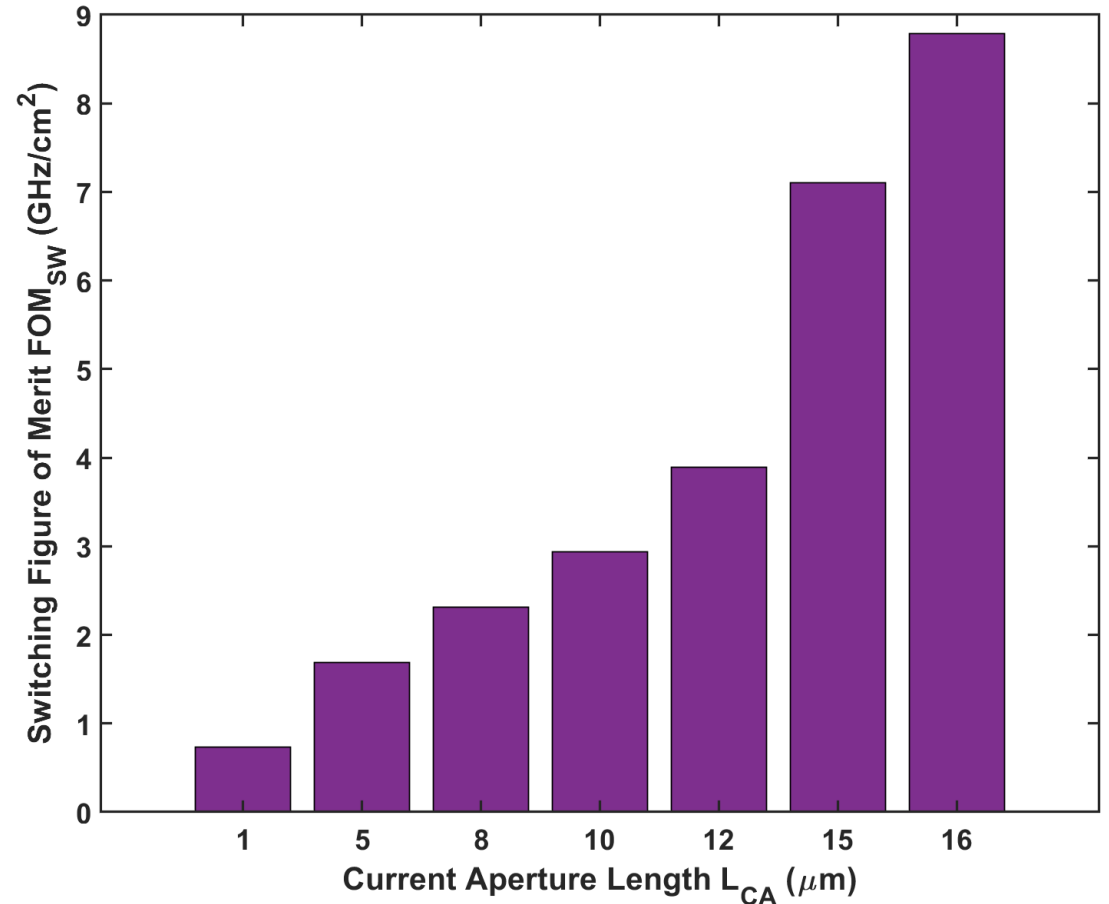
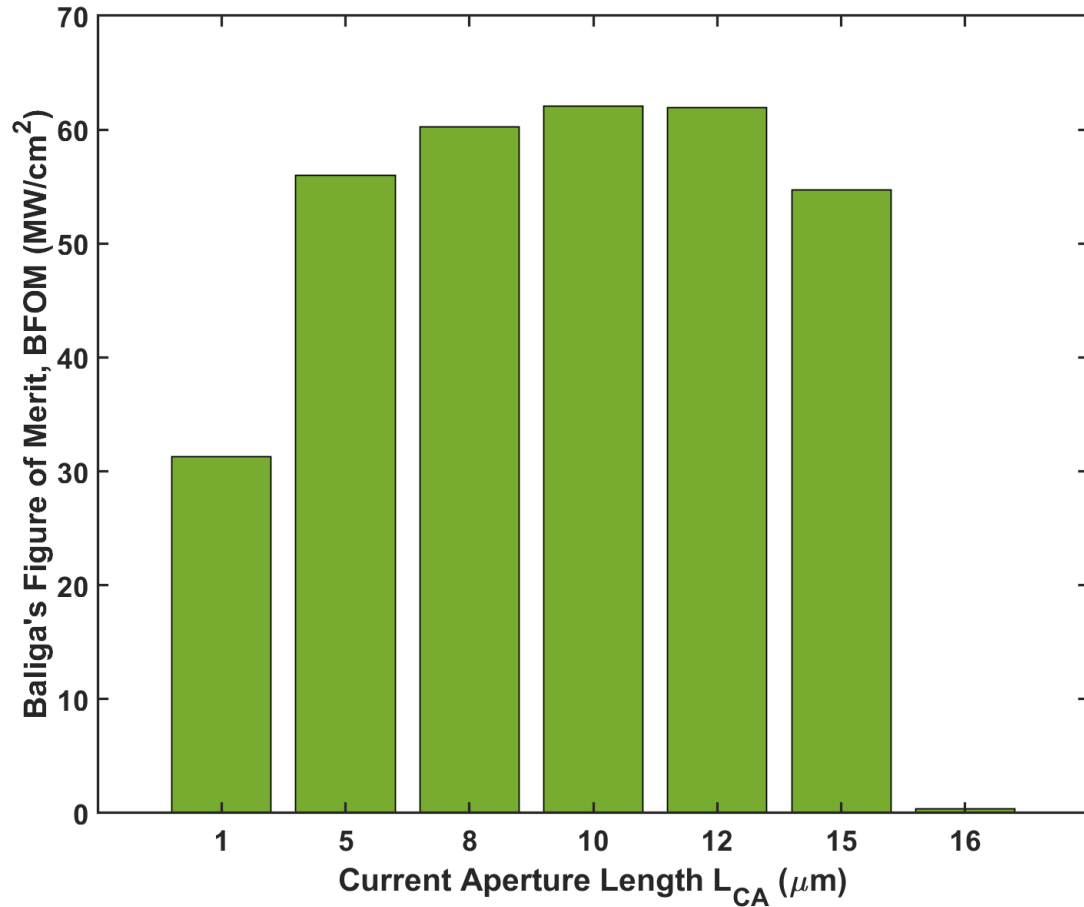
Rectangular-wave oscillator circuit



- Output waveform of oscillator remains sharp for larger aperture length at higher frequencies.



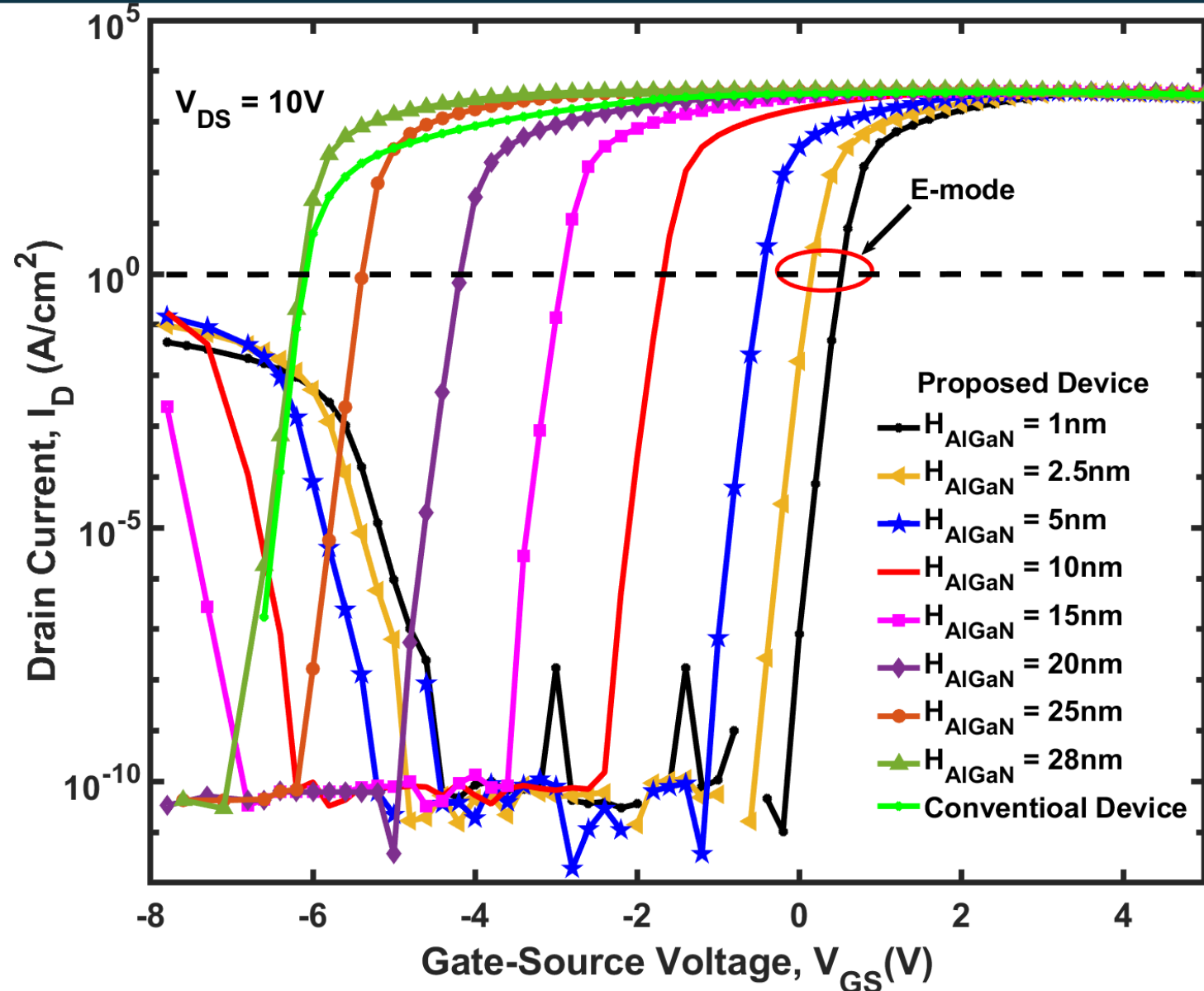
Schematic circuit diagram of a rectangular-wave oscillator circuit.



Comparison of Figure of Merits for various current aperture lengths of CAVET.

- Baliga's Figure of Merit (BFOM) is highest for medium aperture length while Switching Figure of Merit (FOM_{SW}) is highest for large aperture length.
- Considering this trade-off Device with aperture length of 15 μm is best for high power switching applications.

Design of Vertical GaN Device with Superior Performance than Conventional Device



- By adjusting the parameters, an **E-Mode device** can be achieved.

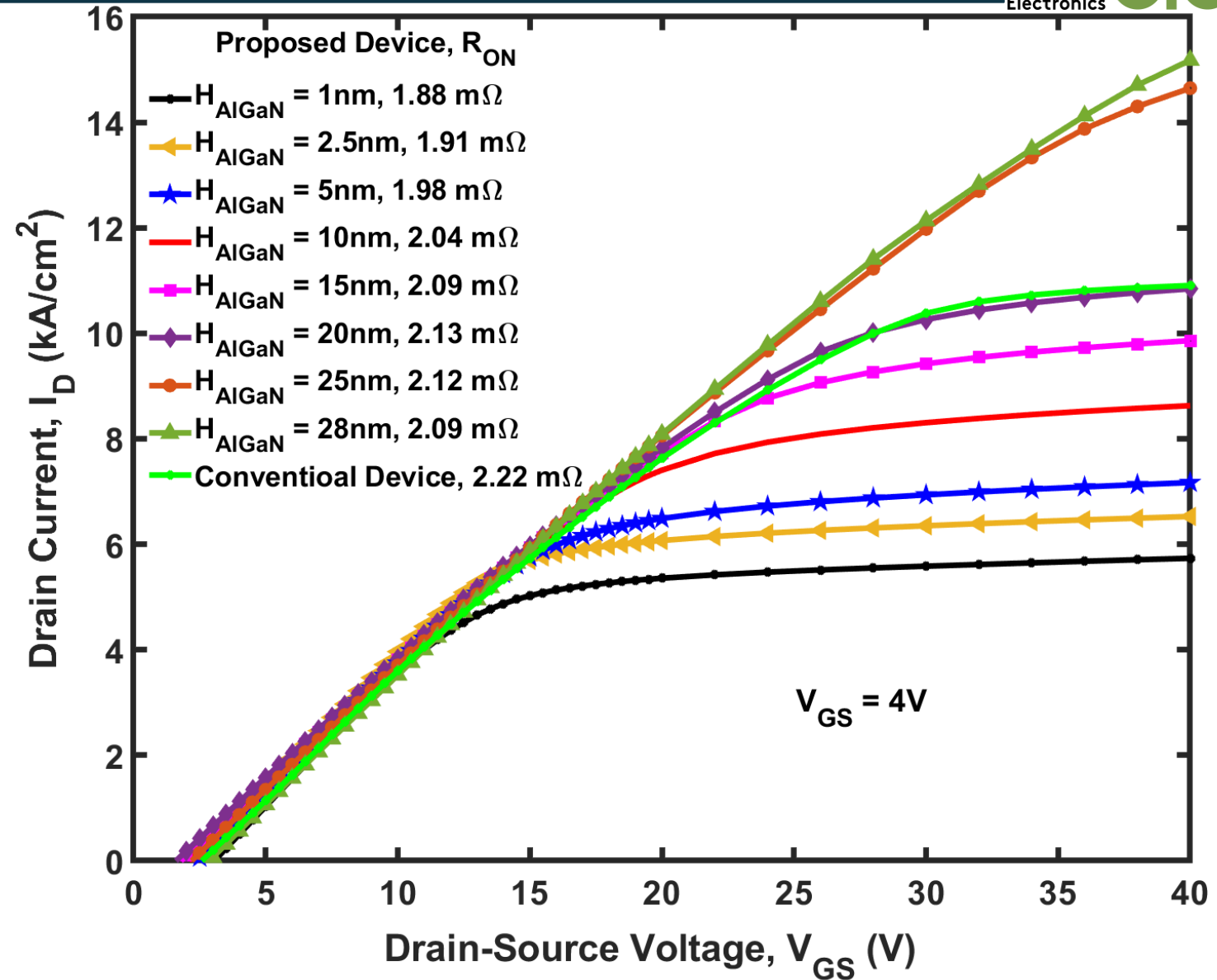
Transfer Characteristics of Conventional and proposed Device at logarithmic Scale

Optimization of On-state Resistance

- **On-Resistance :**

The conventional device is 2.22 m Ω .

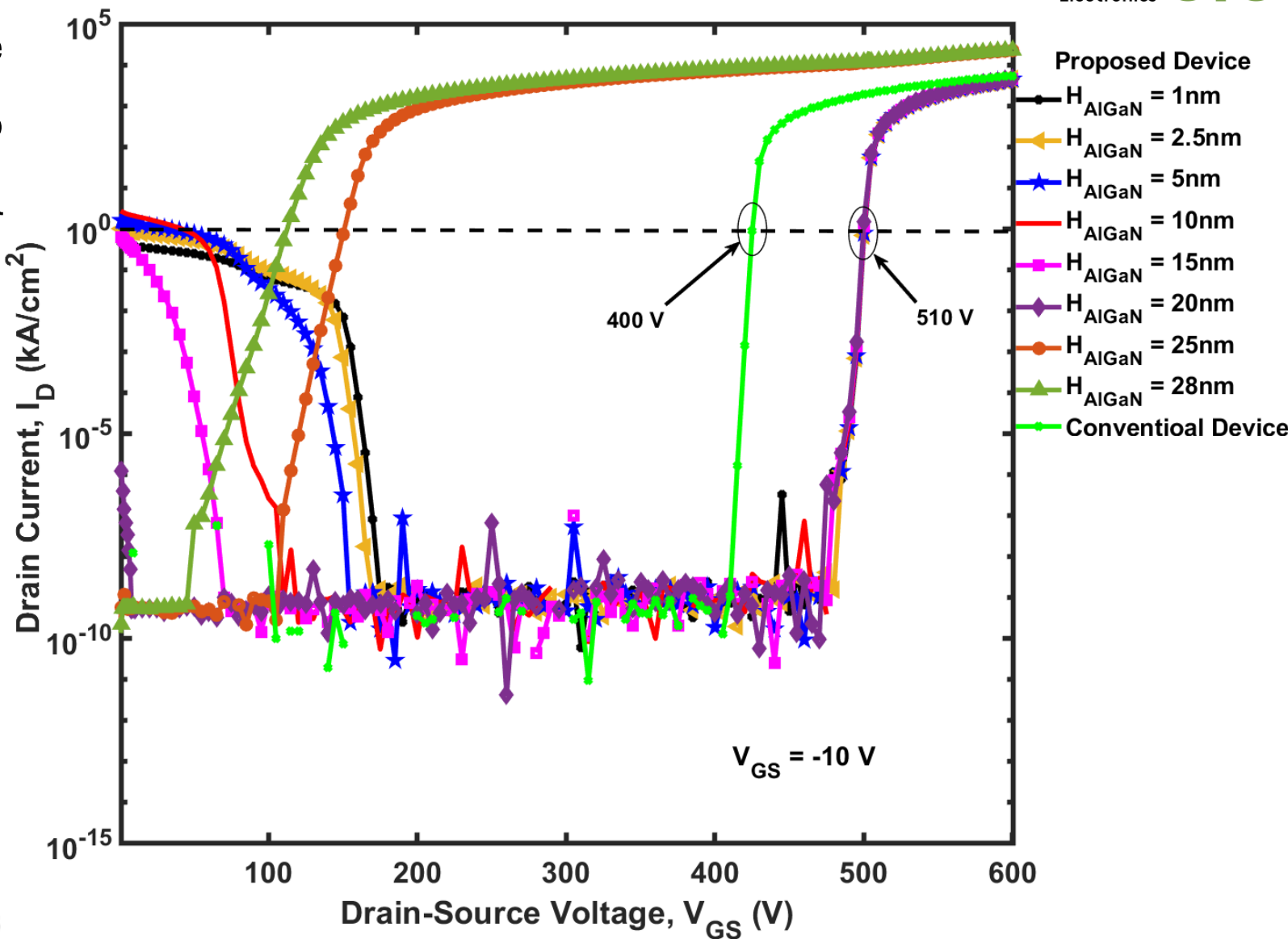
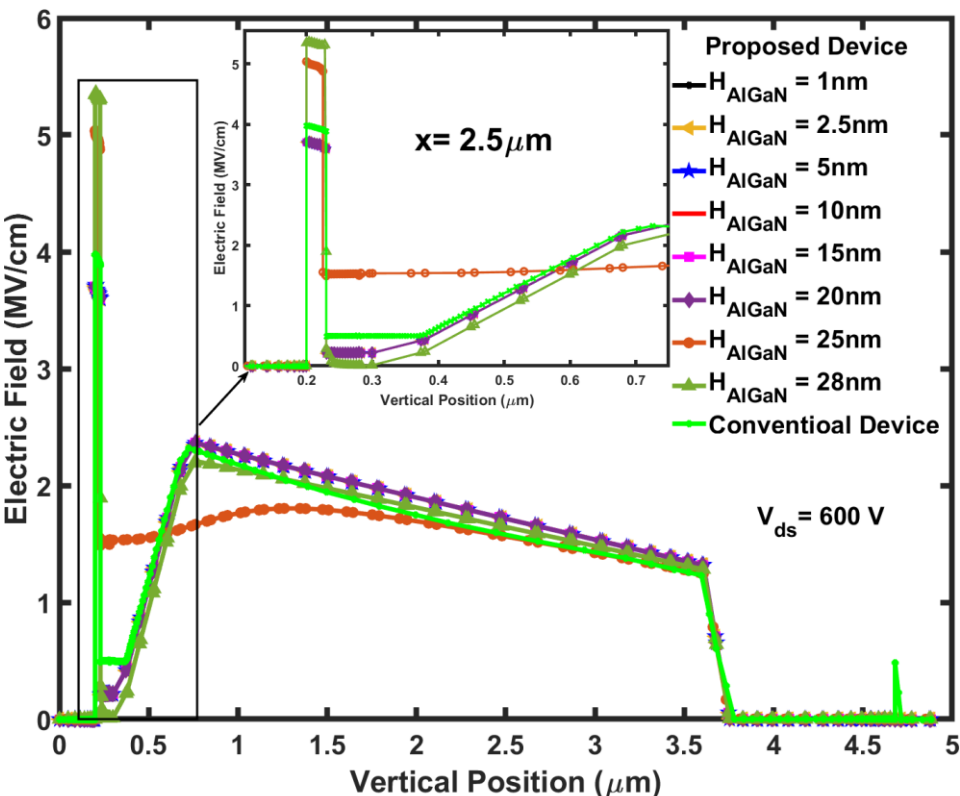
The proposed device is 1.88 m Ω .



Output Characteristics of Conventional and proposed Device.

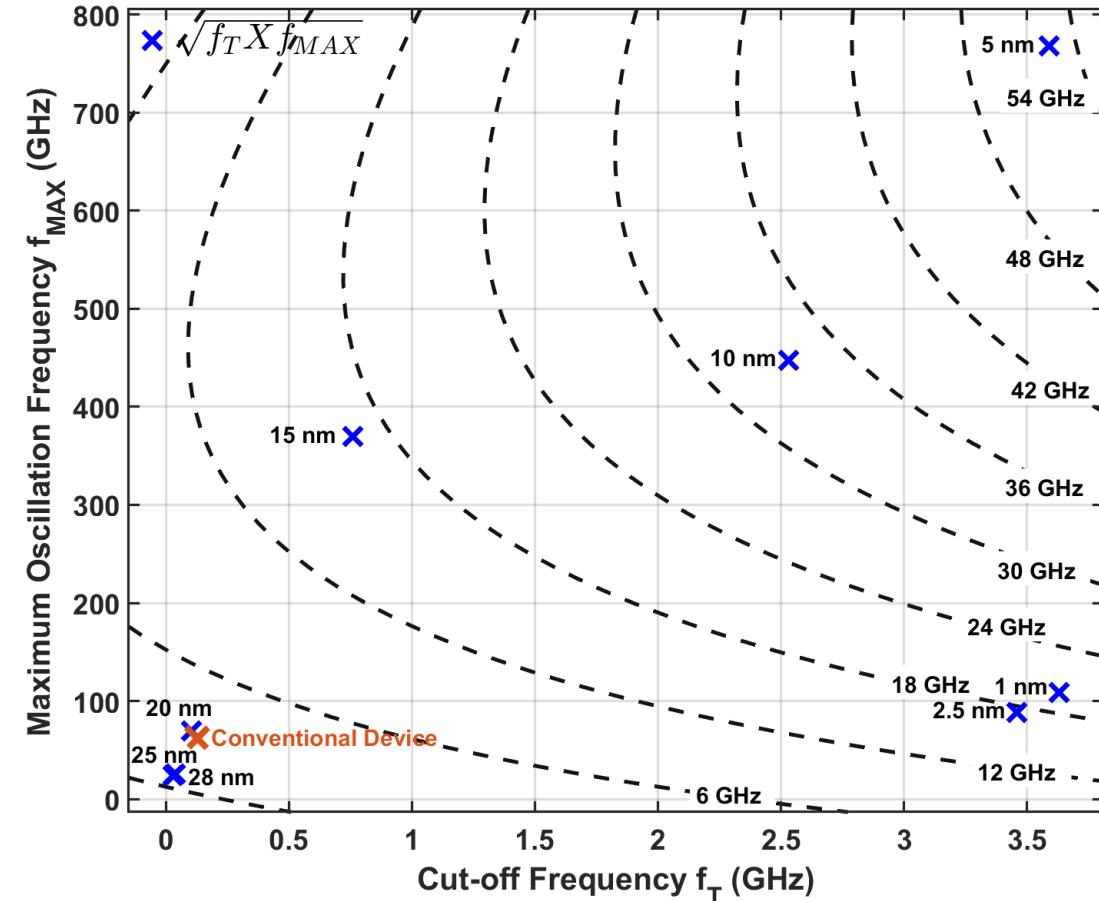
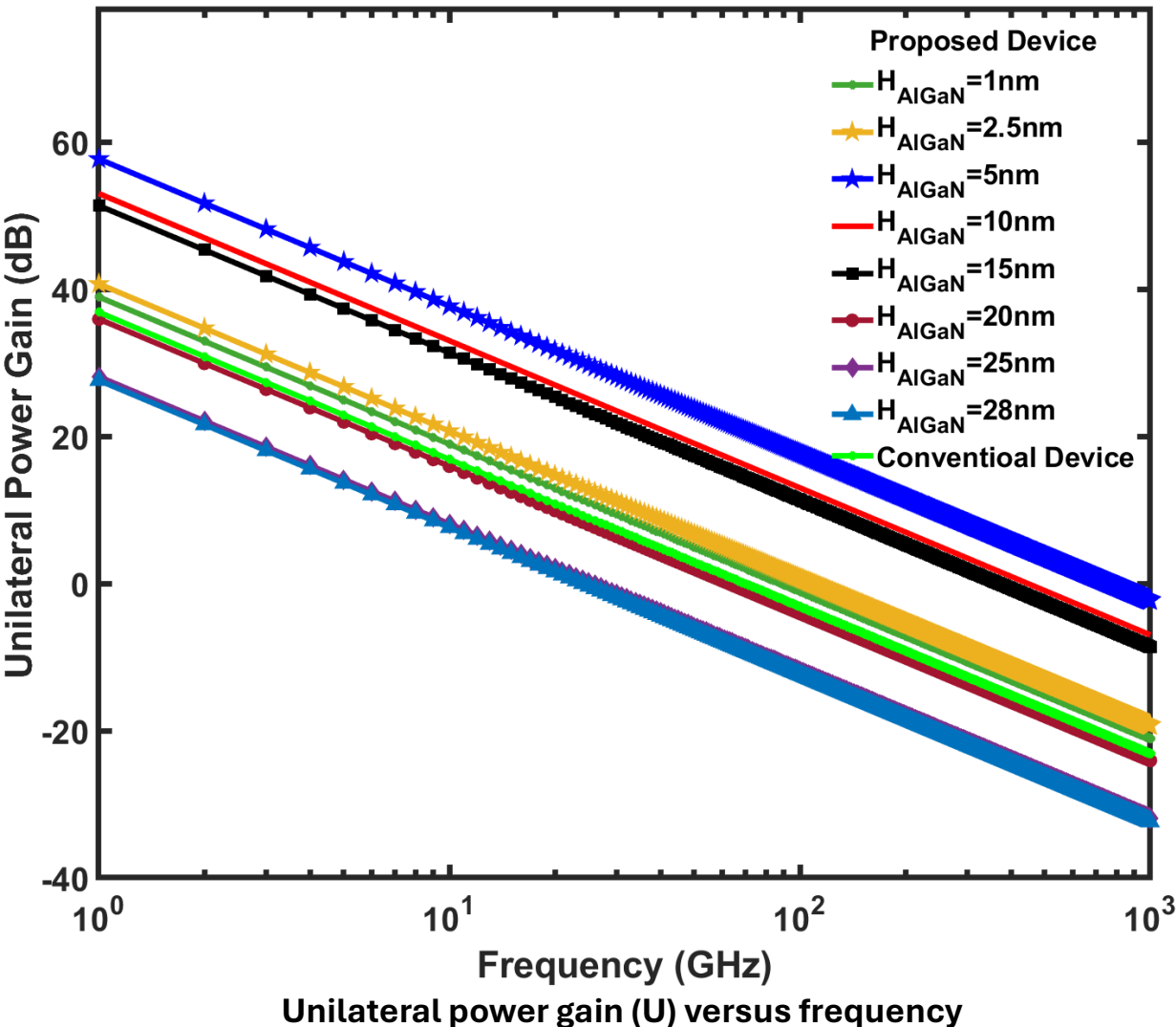
Breakdown Voltage Characteristics

- Addition to the reduced R_{on} , the breakdown voltage is improved to more than 100V than the conventional device.



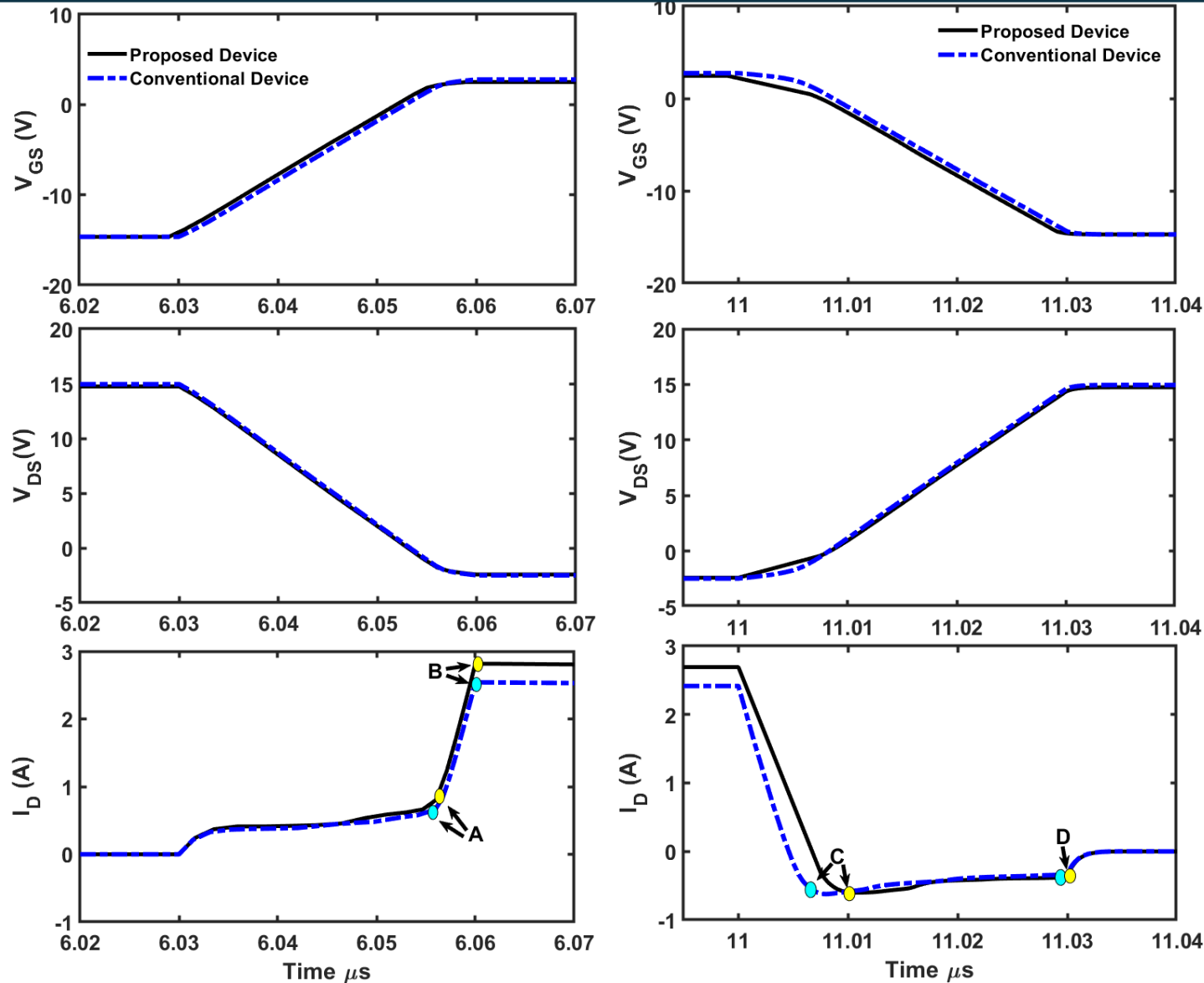
RF Characteristics

- Proposed device achieves a higher Unilateral power gain



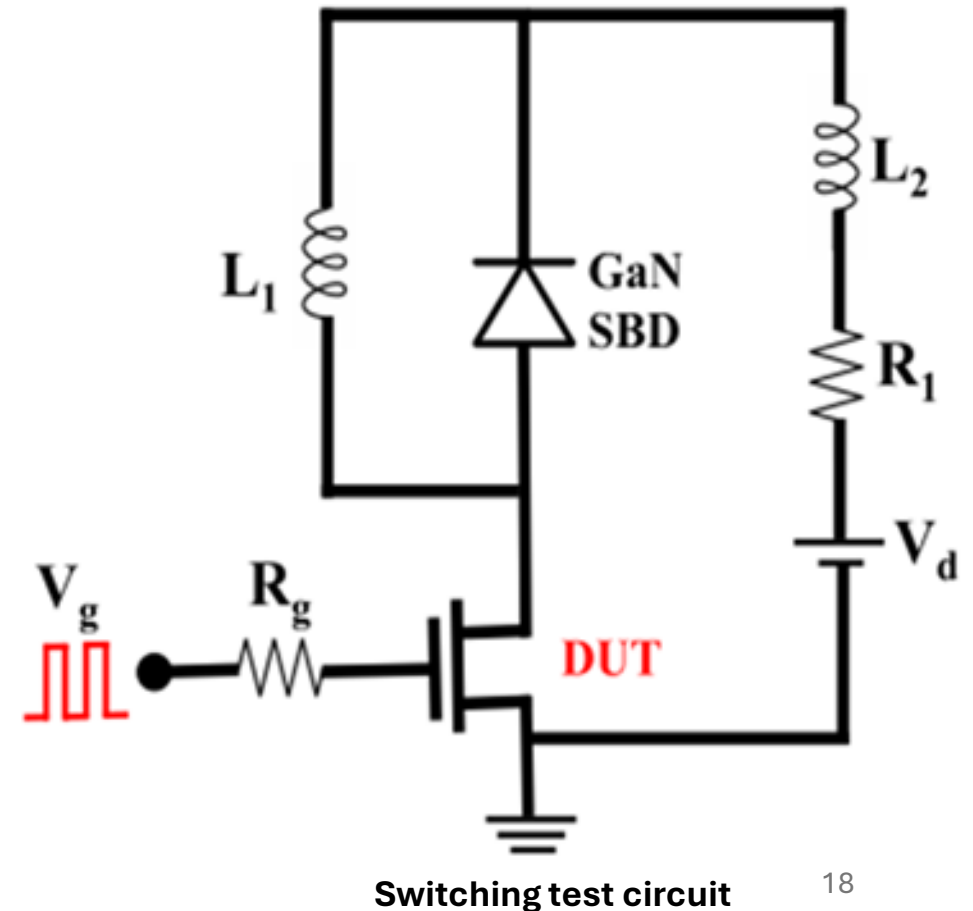
- For proposed device, the f_T and f_{MAX} values increase more than 15 and 10 times respectively.
- The $\sqrt{f_T \times f_{Max}}$ value increases almost 20 times.

Switching Characteristics

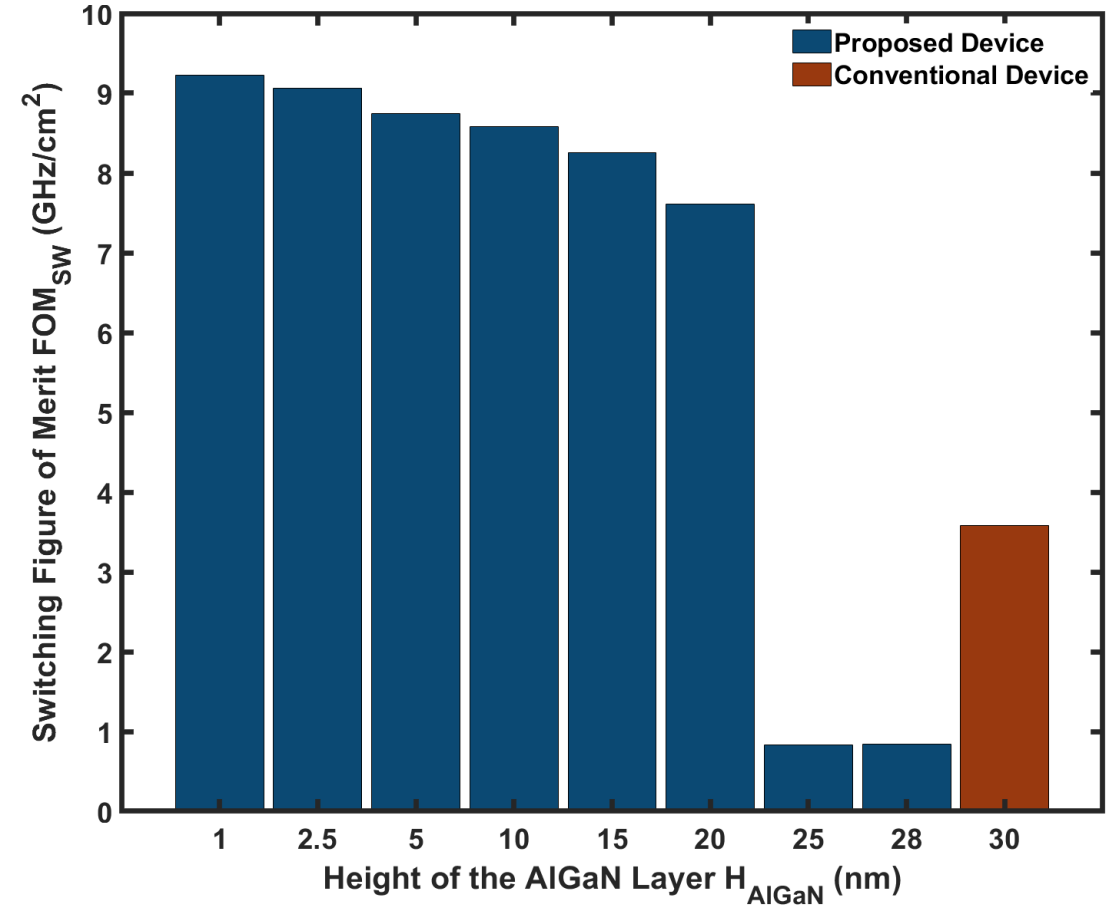
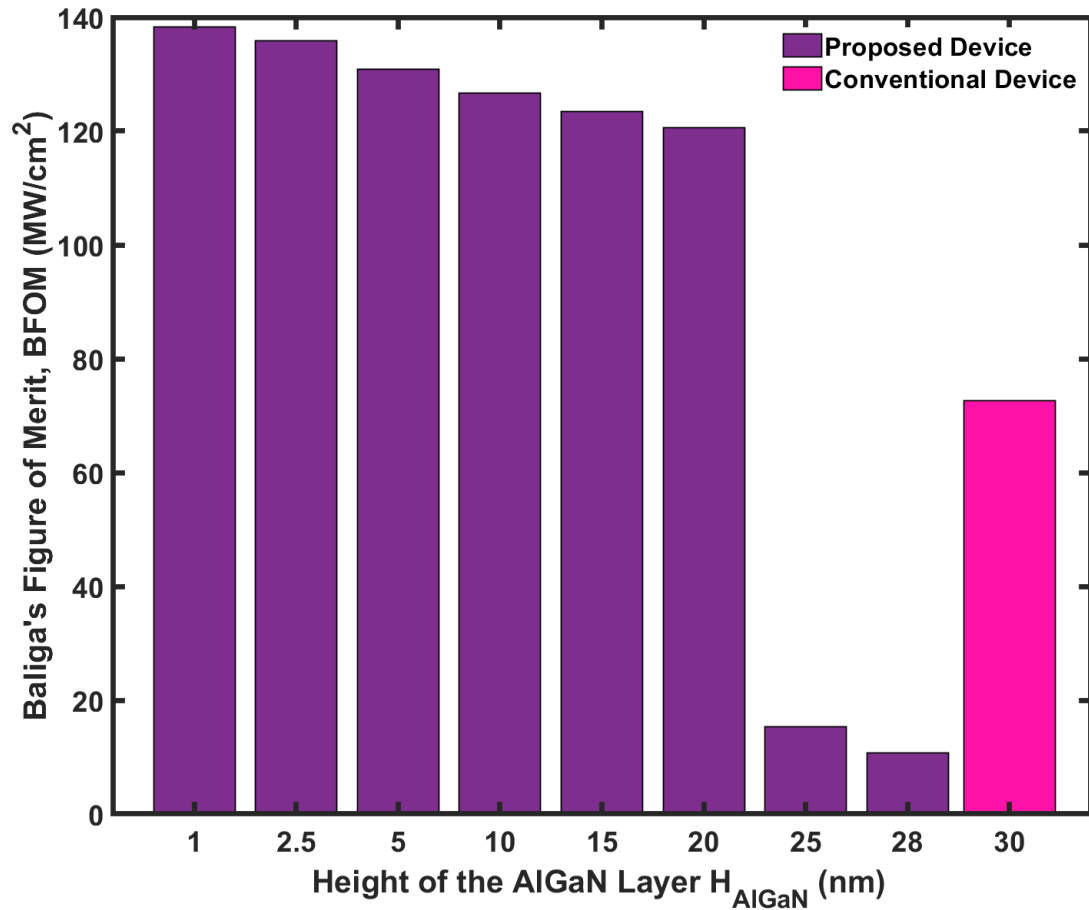


(a) Turn-on and (b) Turn-off voltage/current waveforms for proposed and conventional device

- Proposed device has lower switching time than the conventional device.

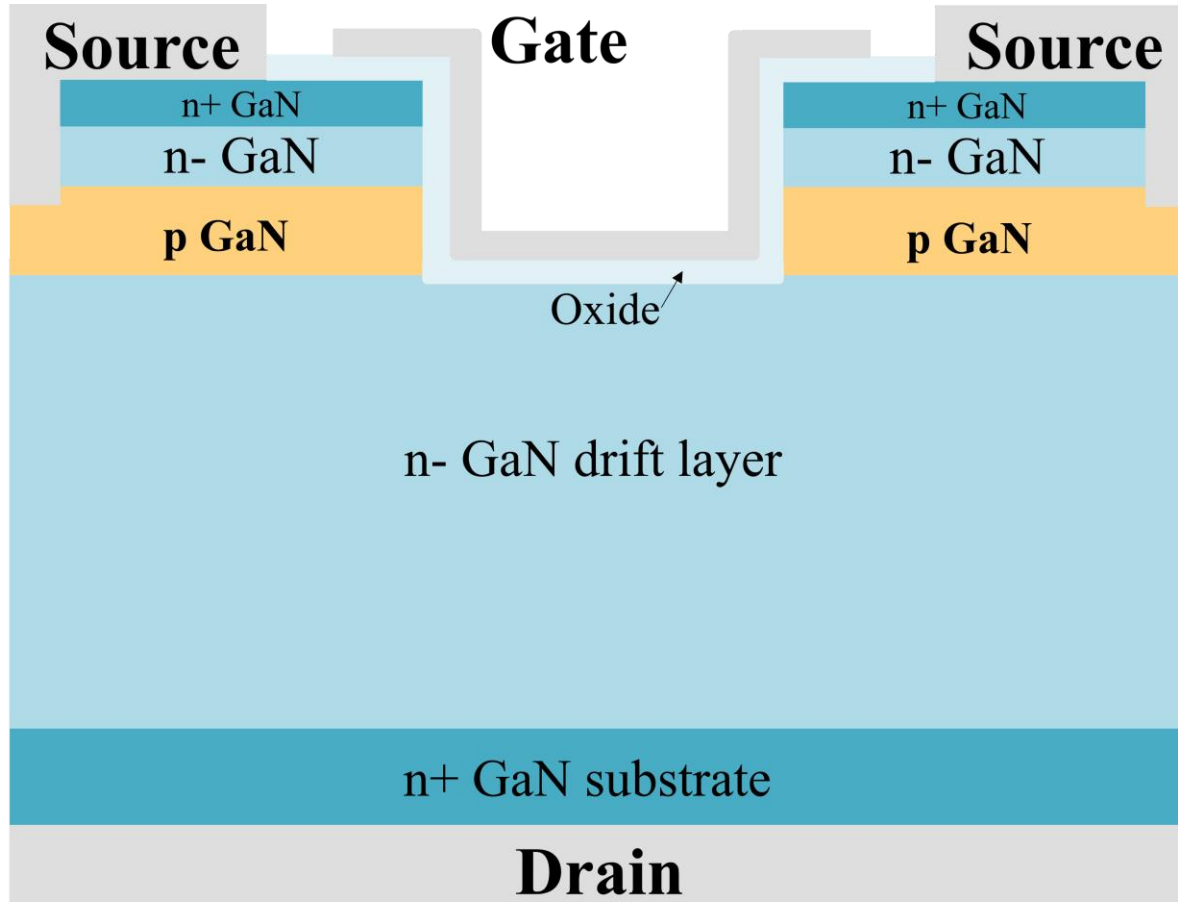


Switching test circuit



Comparison of Figure of Merits for proposed and conventional device.

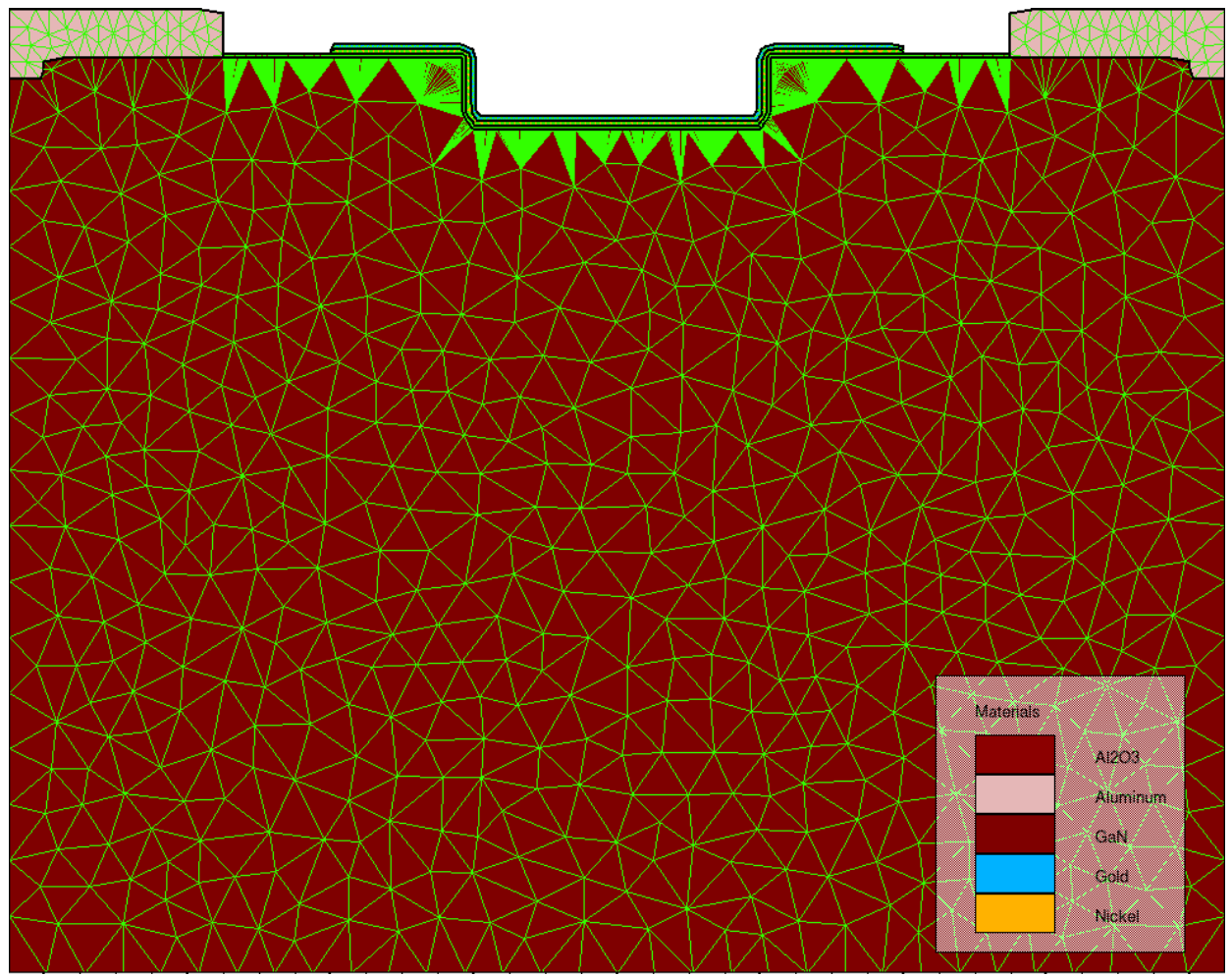
- The Baliga's Figure of Merit (BFOM) and Switching Figure of Merit (FOM_{SW}) both are higher for proposed device than the Conventional Device.



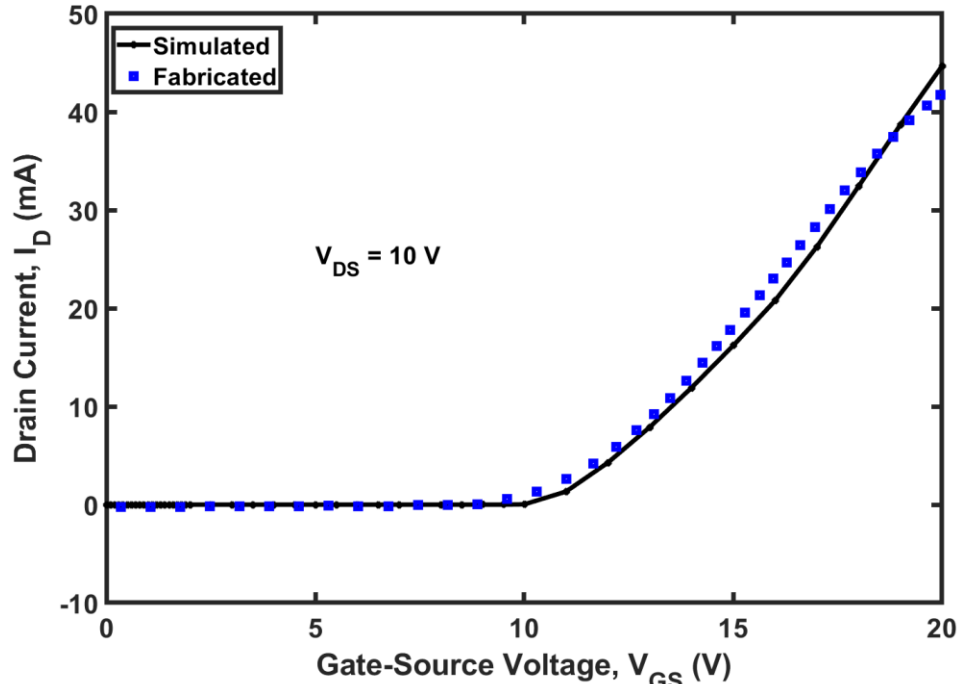
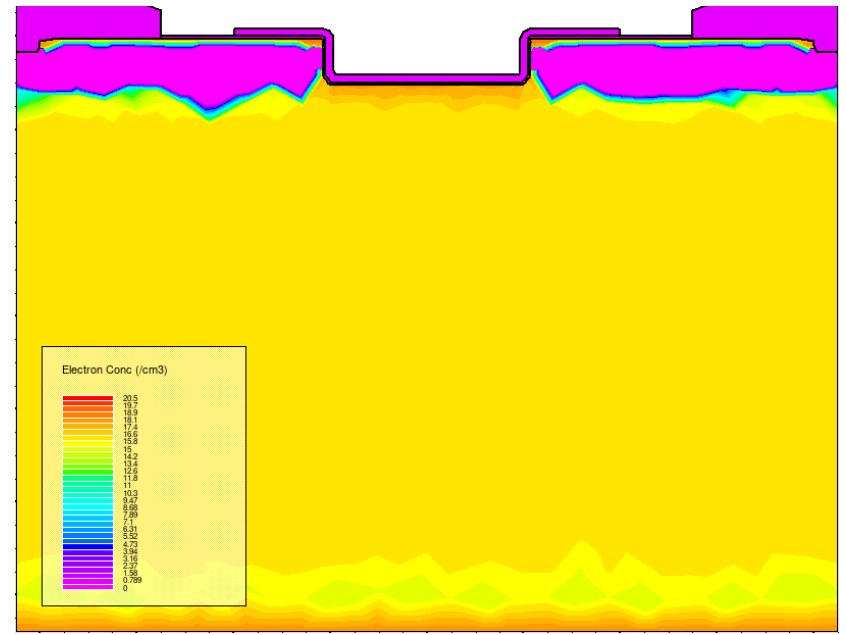
Fabricated GaN Vertical Trench MOSFET

- The active area of the fabricated device is around $5.88 \times 10^{-4} \text{ cm}^2$.
- The threshold voltage is around 10 V.
- The current density around $V_{gs}=11\text{V}$ is 1.5 kAcm^{-2}
- The on-state resistance is $5.8 \text{ m}\Omega \text{ cm}^2$
- And the breakdown voltage of the device is 1.6kV.

Vertical Trench MOSFET (Simulated)



Simulated GaN Vertical Trench MOSFET with meshing





THANK YOU!